

半导体物理及固体物理基础

第四章：非平衡过剩载流子



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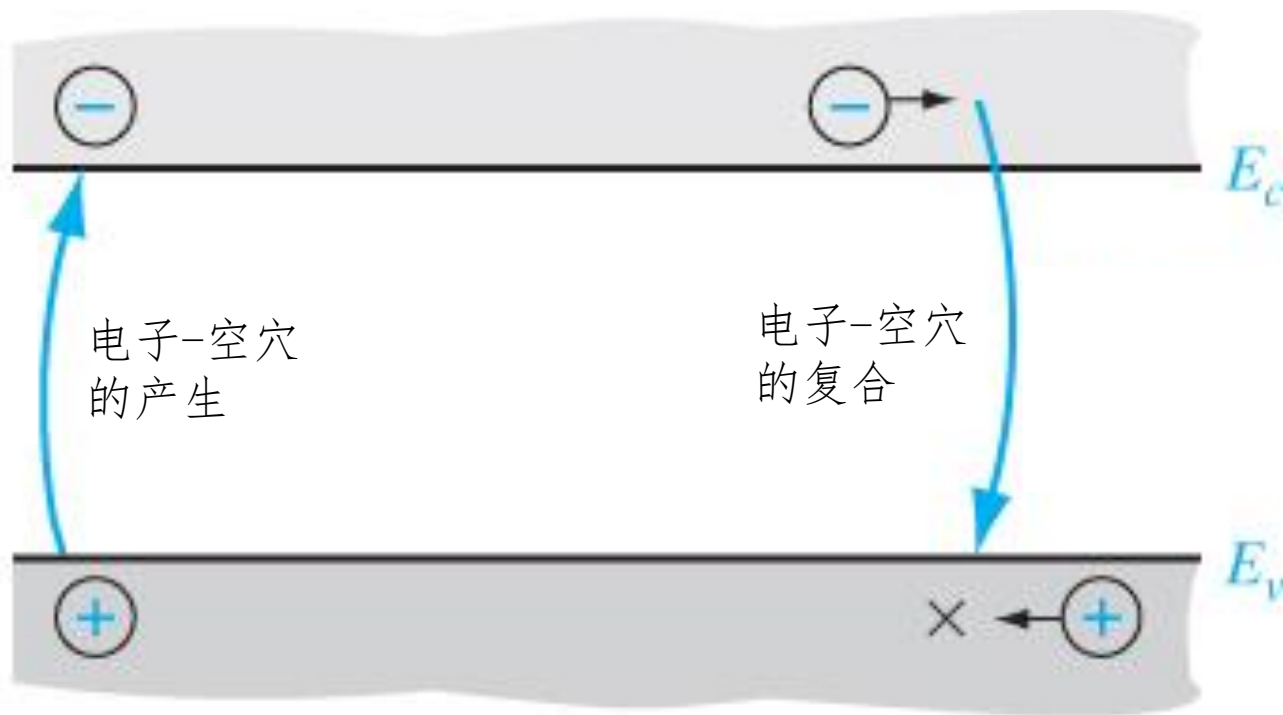
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苏州大学 | 未来科学与工程学院

载流子的产生与复合



直接带间产生、直接带间复合



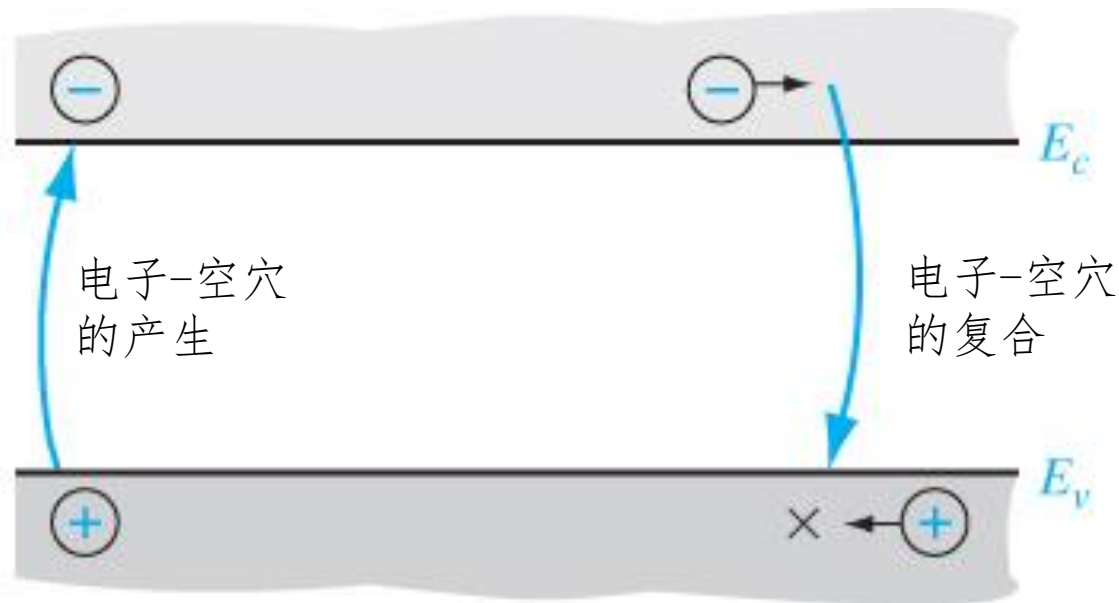
产生 (Generation): 电子和空穴生成的过程

复合 (Recombination): 电子和空穴消失的过程

热平衡状态下的产生和复合



电子和空穴成对产生、成对复合



电子和空穴的产生率: $G_{n0} = G_{p0}$ $\text{\#/cm}^3\text{-s}$

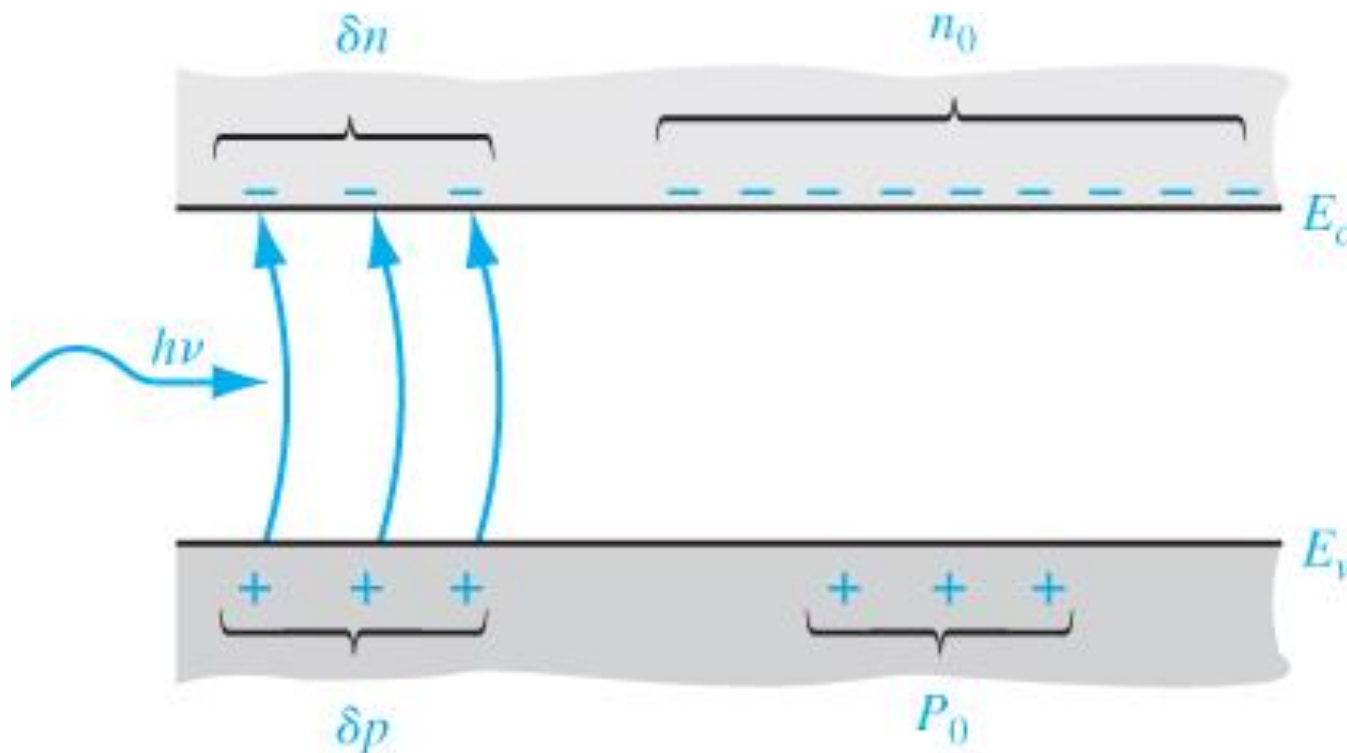
电子和空穴的复合率: $R_{n0} = R_{p0}$ $\text{\#/cm}^3\text{-s}$

热平衡状态下: $G_{n0} = G_{p0} = R_{n0} = R_{p0}$

过剩载流子的产生



高能光子（能量大于禁带宽度）射入半导体，价带电子跃迁进入导带



$$\begin{aligned} n &= n_0 + \delta n \\ p &= p_0 + \delta p \end{aligned}$$

过剩电子、空穴

过剩载流子：

在外界作用下，导带或价带中产生的额外的载流子。

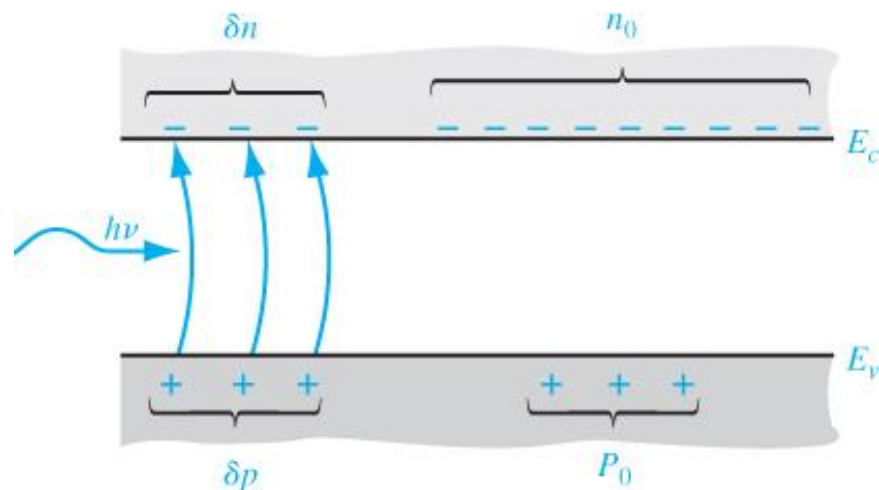
对于直接的带间产生来讲，
过剩电子和空穴也是成对出现的：

$$g_n = g_p$$

产生了过剩载流子之后：

$$n = n_0 + \delta n$$

$$p = p_0 + \delta p$$

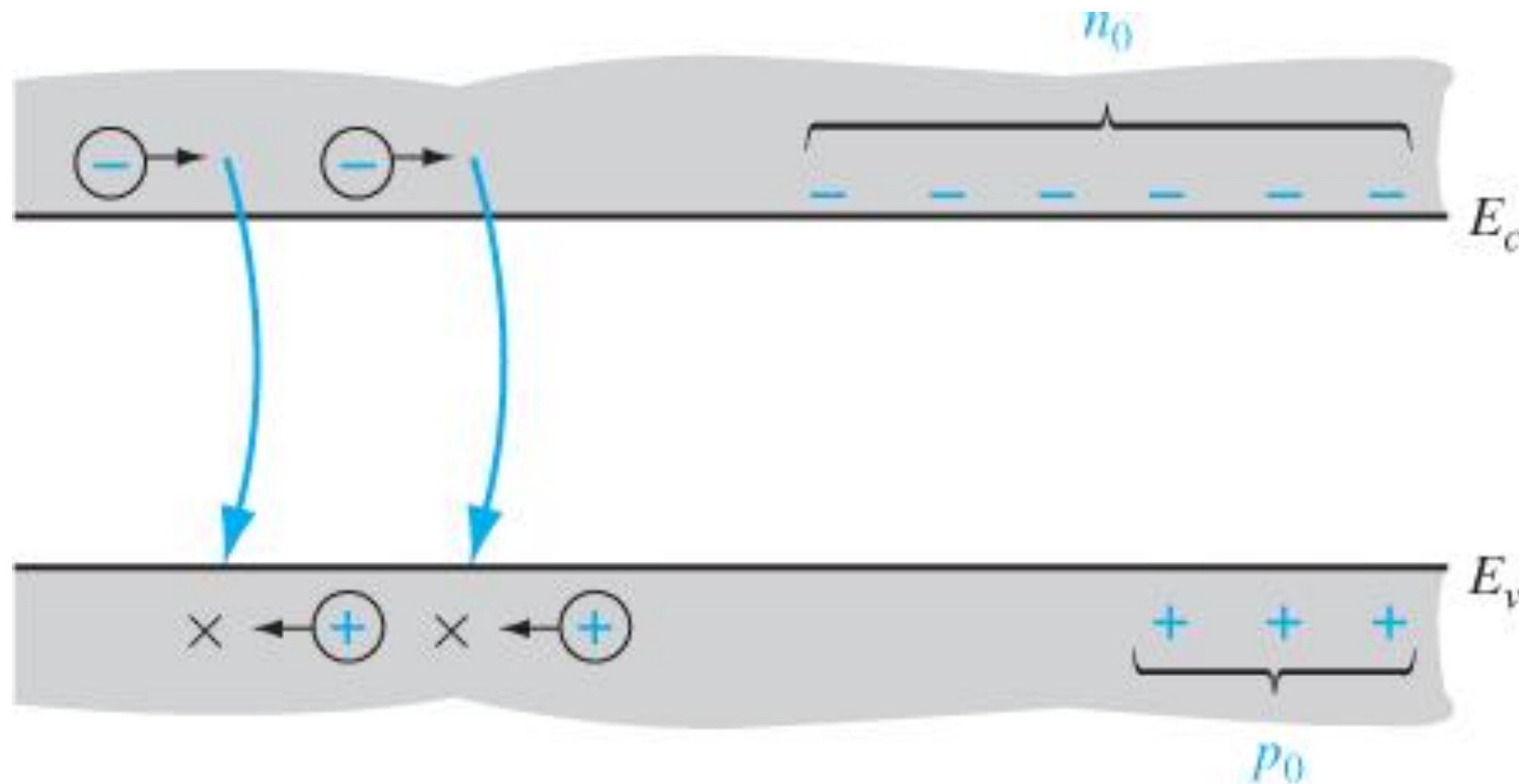


$$np = (n_0 + \delta n)(p_0 + \delta p) \neq n_i^2$$

过剩载流子的复合率



关闭光照后，过剩载流子复合，重建热平衡



过剩电子和空穴也是成对复合的： $R'_n = R'_p$

复合率和电子与空穴的浓度成正比：

热平衡状态下：

$$G_{n0} = R_{n0} = a_r n_0 p_0$$

a_r 是比例系数，与浓度无关

非平衡状态下：

$$R_n = a_r n(t) p(t)$$

$$n(t) = n_0 + \delta n(t) \quad p(t) = p_0 + \delta p(t)$$

电子浓度的变化率：

$$\begin{aligned} n(t) &= n_0 + \delta n(t) \\ p(t) &= p_0 + \delta p(t) \end{aligned}$$

$$\begin{aligned} \frac{dn(t)}{dt} &= a_r n_i^2 - a_r n(t) p(t) \quad \text{↙} \\ &= a_r \left[n_i^2 - (n_0 + \delta n(t))(p_0 + \delta p(t)) \right] \\ &= a_r \left[\textcolor{red}{n_i^2} - \textcolor{red}{n_0 p_0} - n_0 \delta p(t) - p_0 \delta n(t) - \delta n(t) \delta p(t) \right] \\ &= -a_r \delta n(t) \left[(n_0 + p_0) + \delta n(t) \right] \end{aligned}$$

$$\begin{aligned}\frac{d\delta n(t)}{dt} &= -a_r \delta n(t) \left[(n_0 + p_0) + \delta n(t) \right] \\ &= -a_r p_0 \delta n(t)\end{aligned}$$

p 型半导体;

小注入条件 ($\delta n(t) \ll p_0$)

$$\begin{aligned}\delta n(t) &= \delta n(0) e^{-a_r p_0 t} \\ &= \delta n(0) e^{-t/\tau_{n0}}\end{aligned}$$

$\tau_{n0} = \frac{1}{a_r p_0}$, 是一个常数,

τ_{n0} 称为过剩少数载流子(电子)寿命
描述了少数载流子的衰减。

$$\delta n(t) = \delta n(0)e^{-t/\tau_{n0}}$$

过剩少数载流子电子的复合率定义为一个正数：

$$R'_n = -\frac{d\delta n(t)}{dt} = \frac{\delta n(t)}{\tau_{n0}}$$

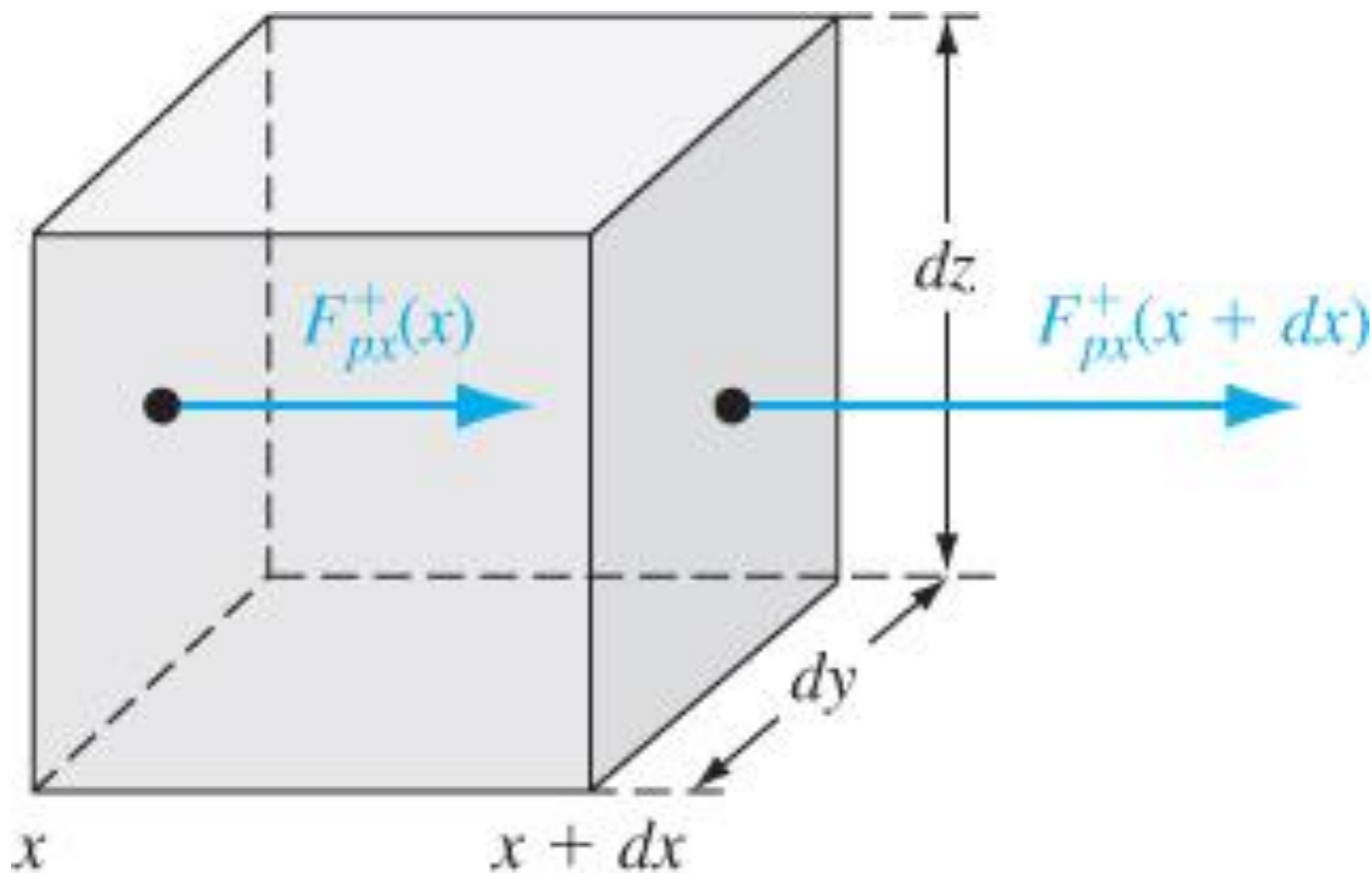
$$R'_n = R'_p$$

小注入条件下的n型半导体：

$$R'_p = \frac{\delta p(t)}{\tau_{p0}}$$

$$\tau_{p0} = \frac{1}{\alpha_r n_0}$$

$$R'_n = R'_p$$



$$\frac{\partial p}{\partial t} = -\frac{\partial F_p^+}{\partial x} + g_p - \frac{p}{\tau_{pt}}$$

$$\frac{\partial n}{\partial t} = -\frac{\partial F_n^-}{\partial x} + g_n - \frac{n}{\tau_{nt}}$$

$$\frac{\partial(\delta p)}{\partial t} = D_p \frac{\partial^2(\delta p)}{\partial x^2} - \mu_p \left(E \frac{\partial(\delta p)}{\partial x} + p \frac{\partial E}{\partial x} \right) + g_p - \frac{p}{\tau_{pt}}$$

$$\frac{\partial(\delta n)}{\partial t} = D_n \frac{\partial^2(\delta n)}{\partial x^2} + \mu_n \left(E \frac{\partial(\delta n)}{\partial x} + n \frac{\partial E}{\partial x} \right) + g_n - \frac{n}{\tau_{nt}}$$

$$\frac{\partial(\delta p)}{\partial t} = D_p \frac{\partial^2(\delta p)}{\partial x^2} - \mu_p \left(\mathbf{E} \frac{\partial(\delta p)}{\partial x} + p \frac{\partial \mathbf{E}}{\partial x} \right) + g_p - \frac{p}{\tau_{pt}}$$

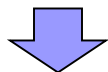
$$\frac{\partial(\delta n)}{\partial t} = D_n \frac{\partial^2(\delta n)}{\partial x^2} + \mu_n \left(\mathbf{E} \frac{\partial(\delta n)}{\partial x} + n \frac{\partial \mathbf{E}}{\partial x} \right) + g_n - \frac{n}{\tau_{pt}}$$

$\mathbf{E} = \mathbf{E}_{app} + \mathbf{E}_{int}$ 假设 $|\mathbf{E}_{int}| \ll |\mathbf{E}_{app}|$, 但是 $\frac{\partial \mathbf{E}}{\partial x}$ 不可忽略

$$\frac{\partial \mathbf{E}}{\partial x} = \frac{\partial(\mathbf{E}_{app} + \mathbf{E}_{int})}{\partial x} = \frac{\partial \mathbf{E}_{int}}{\partial x}$$

$$\because \delta p = \delta n$$

$$\frac{\partial(\delta p)}{\partial t} = D_p \frac{\partial^2(\delta p)}{\partial x^2} - \mu_p \left(E \frac{\partial(\delta p)}{\partial x} + p \frac{\partial E}{\partial x} \right) + g_p - \frac{p}{\tau_{pt}}$$

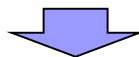


$$\frac{\partial(\delta n)}{\partial t} = D_p \frac{\partial^2(\delta n)}{\partial x^2} - \mu_p \left(E \frac{\partial(\delta n)}{\partial x} + p \frac{\partial E}{\partial x} \right) + g_p - \frac{p}{\tau_{pt}}$$

$$\frac{\partial(\delta n)}{\partial t} = D_n \frac{\partial^2(\delta n)}{\partial x^2} + \mu_n \left(E \frac{\partial(\delta n)}{\partial x} + n \frac{\partial E}{\partial x} \right) + g_n - \frac{n}{\tau_{pt}}$$

$$\frac{\partial(\delta n)}{\partial t} = D_p \frac{\partial^2(\delta n)}{\partial x^2} - \mu_p \left(E \frac{\partial(\delta n)}{\partial x} + \boxed{p \frac{\partial E}{\partial x}} \right) + g - R$$

$$\frac{\partial(\delta n)}{\partial t} = D_n \frac{\partial^2(\delta n)}{\partial x^2} + \mu_n \left(E \frac{\partial(\delta n)}{\partial x} + \boxed{n \frac{\partial E}{\partial x}} \right) + g - R$$



$$\frac{\partial(\delta n)}{\partial t} = D' \frac{\partial^2(\delta n)}{\partial x^2} + \mu' E \frac{\partial(\delta n)}{\partial x} + g - R$$

$$\frac{\partial(\delta n)}{\partial t} = D' \frac{\partial^2(\delta n)}{\partial x^2} + \mu' E \frac{\partial(\delta n)}{\partial x} + g - R$$

$$D' = \frac{\mu_n n D_p + \mu_p p D_n}{\mu_n n + \mu_p p} \quad \mu' = \frac{\mu_n \mu_p (p - n)}{\mu_n n + \mu_p p}$$

双极扩散系数:

$$D' = \frac{\mu_n n D_p + \mu_p p D_n}{\mu_n n + \mu_p p}$$

$$D' = \frac{D_n D_p (n + p)}{D_n n + D_p p}$$

$$\frac{D_n}{\mu_n} = \frac{D_p}{\mu_p} = \frac{kT}{e}$$

双极迁移率:

$$\mu' = \frac{\mu_n \mu_p (p - n)}{\mu_n n + \mu_p p}$$

$$\begin{aligned} D' &= \frac{D_n D_p (n + p)}{D_n n + D_p p} \\ &= \frac{D_n D_p [(n_0 + \delta n) + (p_0 + \delta p)]}{D_n (n_0 + \delta n) + D_p (p_0 + \delta p)} \end{aligned}$$

$$\begin{aligned} \mu' &= \frac{\mu_n \mu_p (p - n)}{\mu_n n + \mu_p p} \\ &= \frac{\mu_n \mu_p [(p_0 + \delta p) - (n_0 + \delta n)]}{\mu_n (n_0 + \delta n) + \mu_p (p_0 + \delta p)} \end{aligned}$$

$$D' = \frac{D_n D_p \left[(n_0 + \delta n) + (p_0 + \delta p) \right]}{D_n (n_0 + \delta n) + D_p (p_0 + \delta p)}$$

$$\mu' = \frac{\mu_n \mu_p \left[(p_0 + \delta p) - (n_0 + \delta n) \right]}{\mu_n (n_0 + \delta n) + \mu_p (p_0 + \delta p)}$$

对于p型半导体: $n_0 \ll p_0$ $\delta n \ll p_0$

$$D' = D_n \quad \mu' = \mu_n$$

对于n型半导体: $n_0 \gg p_0$ $\delta n \gg p_0$

$$D' = D_p \quad \mu' = -\mu_p$$

$$\frac{\partial(\delta n)}{\partial t} = D' \frac{\partial^2(\delta n)}{\partial x^2} + \mu' E \frac{\partial(\delta n)}{\partial x} + [g - R]$$

$$D' = \frac{\mu_n n D_p + \mu_p p D_n}{\mu_n n + \mu_p p} \quad \mu' = \frac{\mu_n \mu_p (p - n)}{\mu_n n + \mu_p p}$$

双极输运方程中电子的产生率和复合率：

$$\begin{aligned} g - R &= g_n - R_n \\ &= (G_{n0} + g'_n) - (R_{n0} + R'_n) \\ &= g'_n - R'_n \\ &= g'_n - \frac{\delta n}{\tau_n} \end{aligned}$$

电子和空穴的复合率相等：

$$R_n = R_p = \frac{n}{\tau_{nt}} = \frac{p}{\tau_{pt}}$$

$\frac{1}{\tau_{nt}} = \alpha_r p \approx \alpha_r p_0$, 单位时间内电子遇到空穴发生复合的概率
多数载流子空穴的浓度几乎不变,

$$\tau_{nt} = \tau_{n0}$$

小注入条件下的n型半导体：

$\frac{1}{\tau_{pt}} = \alpha_r n \approx \alpha_r n_0$, 单位时间内空穴遇到电子发生复合的概率
多数载流子电子的浓度几乎不变,

$$\tau_{pt} = \tau_{p0}$$

双极输运方程中电子的产生率和复合率：

$$\begin{aligned} g - R &= g_n - R_n \\ &= (G_{n0} + g'_n) - (R_{n0} + R'_n) \\ &= g'_n - R'_n \\ &= g'_n - \frac{\delta n}{\tau_n} \\ &= g' - \frac{\delta n}{\tau_{n0}} \end{aligned} \quad g'_n = g'_p = g'$$

双极输运方程中空穴的产生率和复合率：

$$\begin{aligned} g - R &= g_p - R_p \\ &= (G_{p0} + g_p') - (R_{p0} + R_p') \\ &= g_p' - R_p' \\ &= g_p' - \frac{\delta p}{\tau_p} \\ &= g' - \frac{\delta p}{\tau_{p0}} \end{aligned} \quad g_n' = g_p' = g'$$

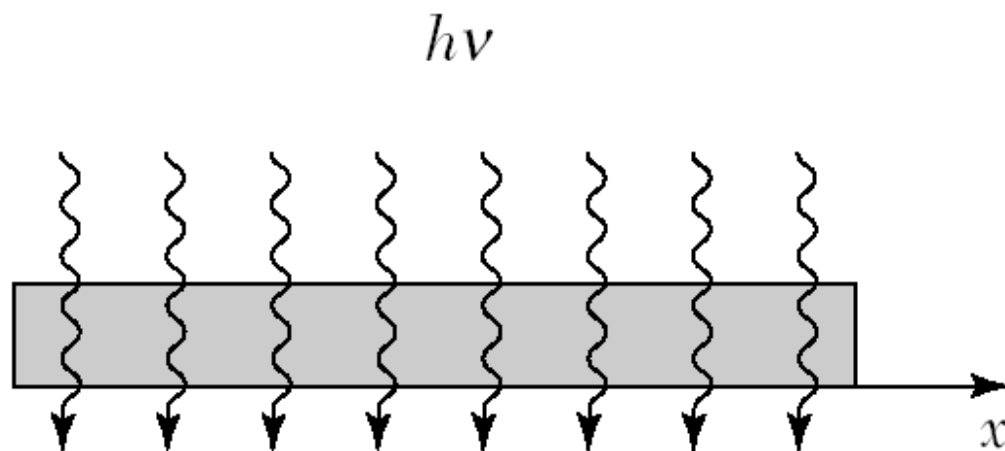
双极输运方程就可以写成少子参数项的形式：

$$\frac{\partial(\delta n)}{\partial t} = D_n \frac{\partial^2(\delta n)}{\partial x^2} + \mu_n E \frac{\partial(\delta n)}{\partial x} + g' - \frac{\delta n}{\tau_{n0}}$$

$$\frac{\partial(\delta p)}{\partial t} = D_p \frac{\partial^2(\delta p)}{\partial x^2} - \mu_p E \frac{\partial(\delta p)}{\partial x} + g' - \frac{\delta p}{\tau_{p0}}$$

过剩少子的空间和时间函数就可以通过少子的漂移、扩散、产生和复合来描述。

过剩多子的状态就可以由少子的参数来决定。



n 型半导体

$t \geq 0$ 时, 均匀的产生率 g'

满足小注入条件

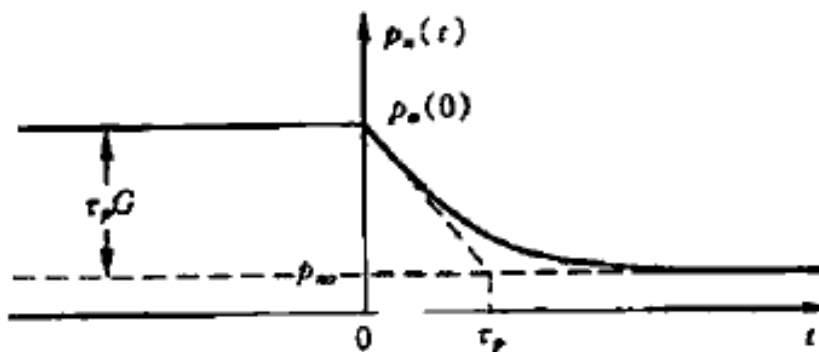
$$\frac{\partial(\delta n)}{\partial t} = D_n \frac{\partial^2(\delta n)}{\partial x^2} + \mu_n E \frac{\partial(\delta n)}{\partial x} + g' - \frac{\delta n}{\tau_{n0}}$$

$$\frac{\partial(\delta p)}{\partial t} = D_p \frac{\partial^2(\delta p)}{\partial x^2} - \mu_p E \frac{\partial(\delta p)}{\partial x} + g' - \frac{\delta p}{\tau_{p0}}$$

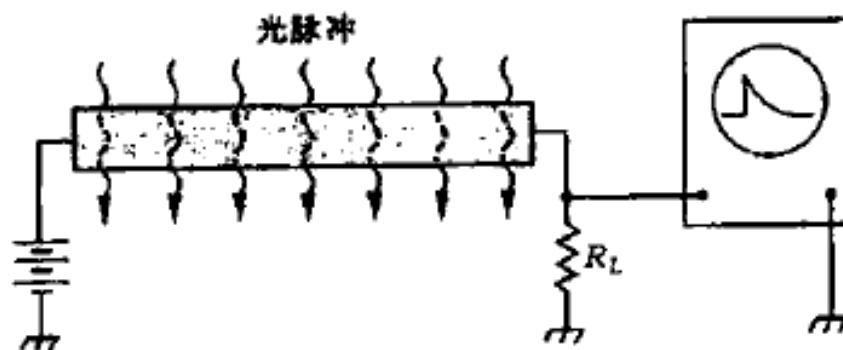
双极输运方程的应用II



(a)



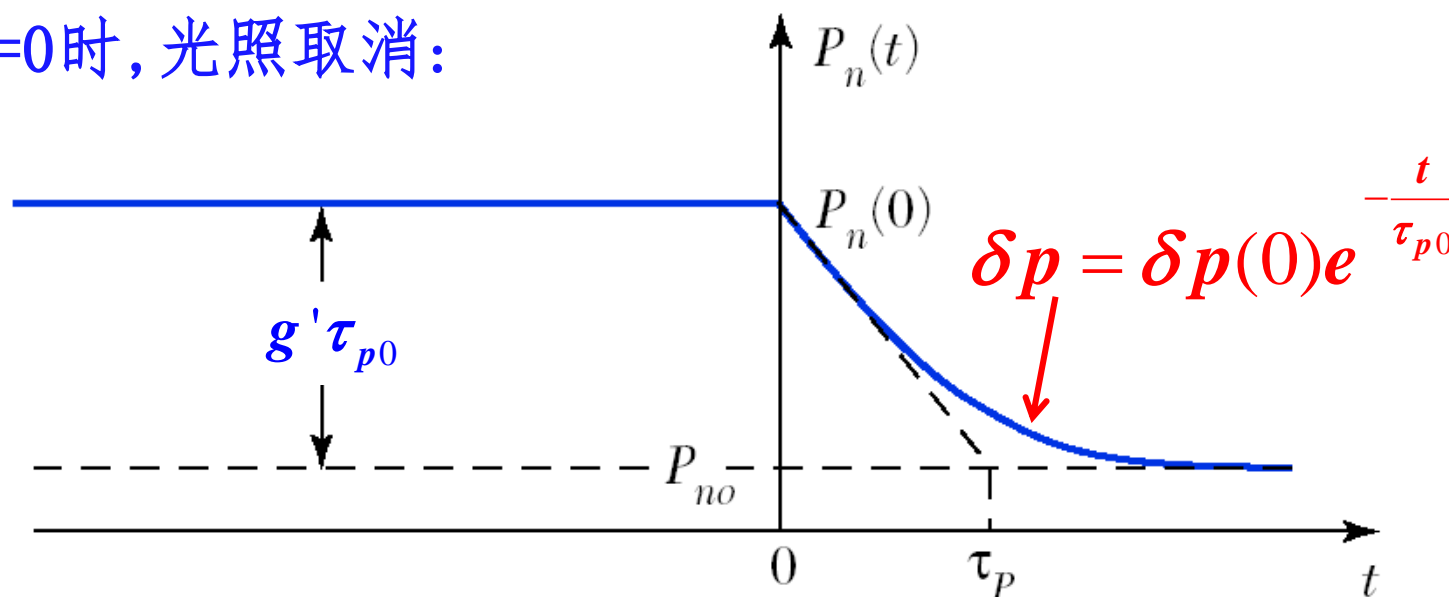
(b)

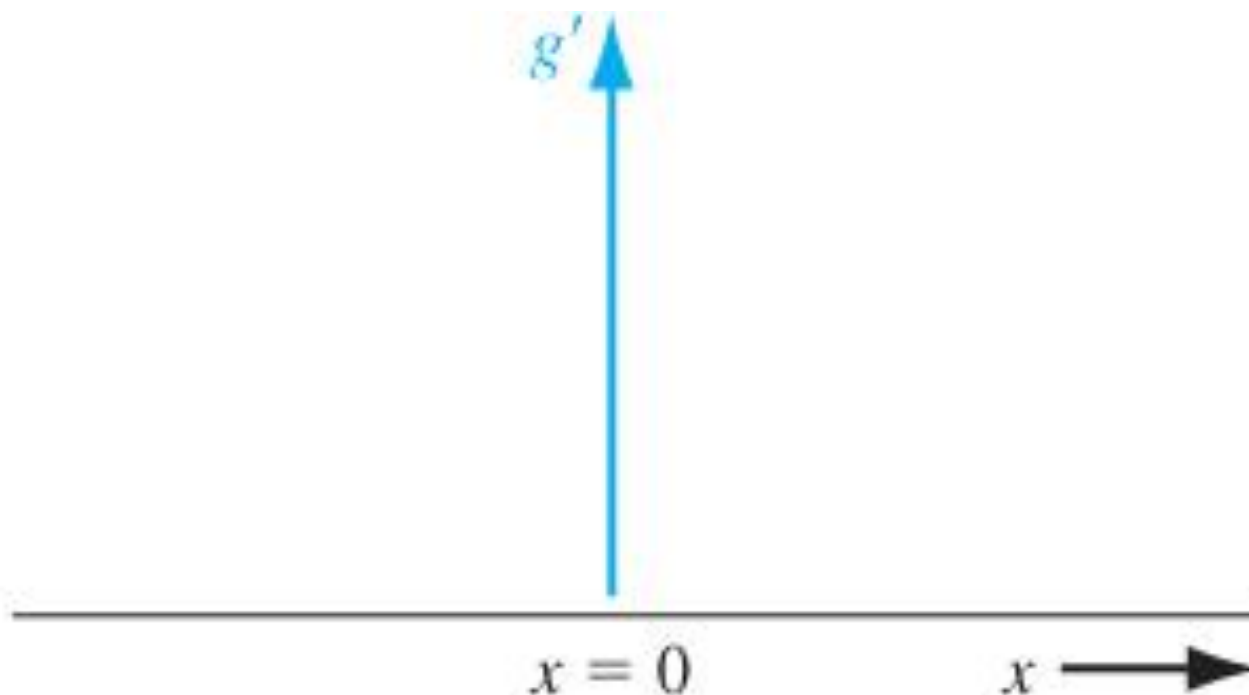


(c)

$$\frac{\partial(\delta p)}{\partial t} = D_p \frac{\partial^2(\delta p)}{\partial x^2} - \mu_p E \frac{\partial(\delta p)}{\partial x} + g' - \frac{\delta p}{\tau_{p0}}$$

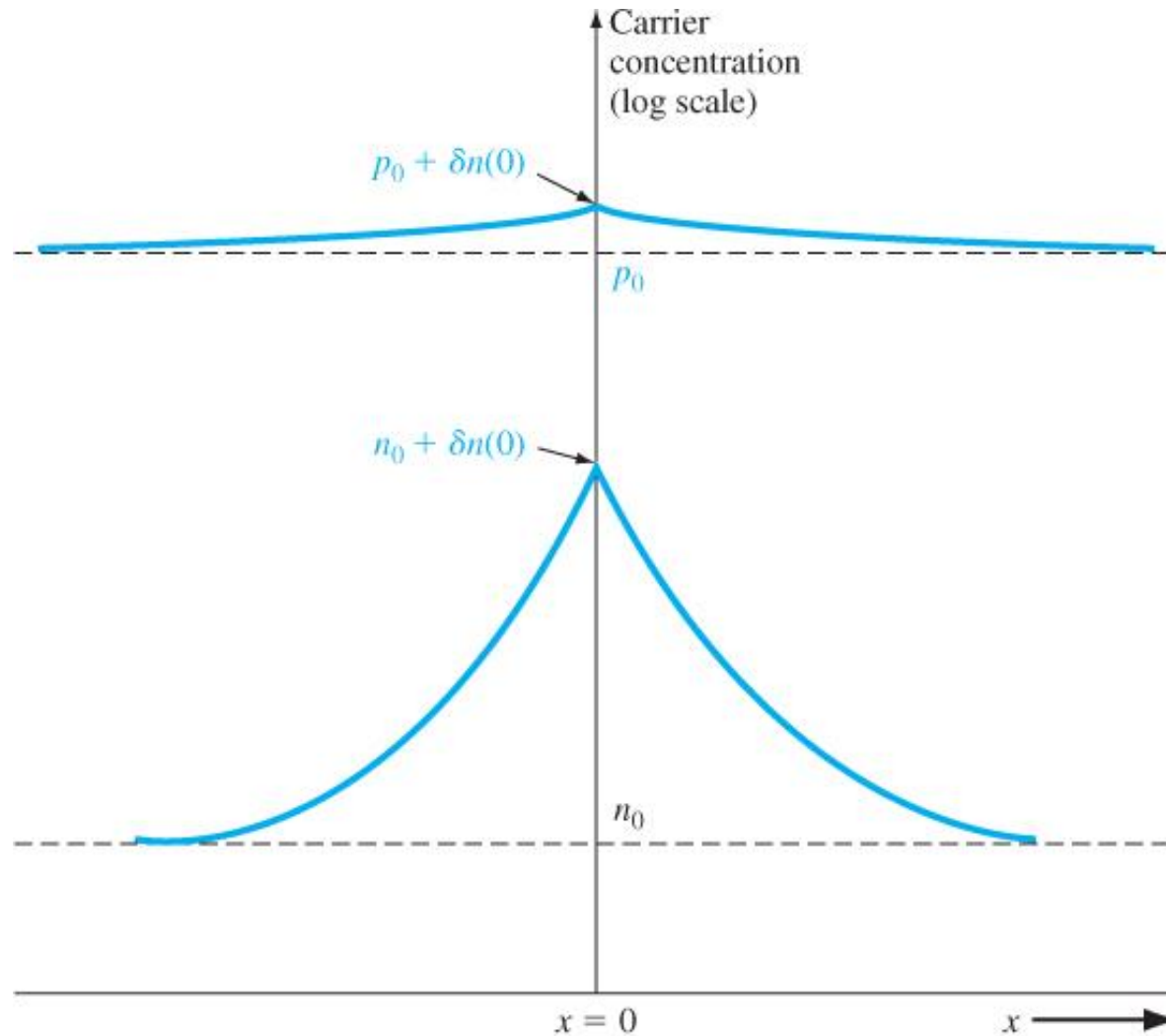
t=0时, 光照取消:



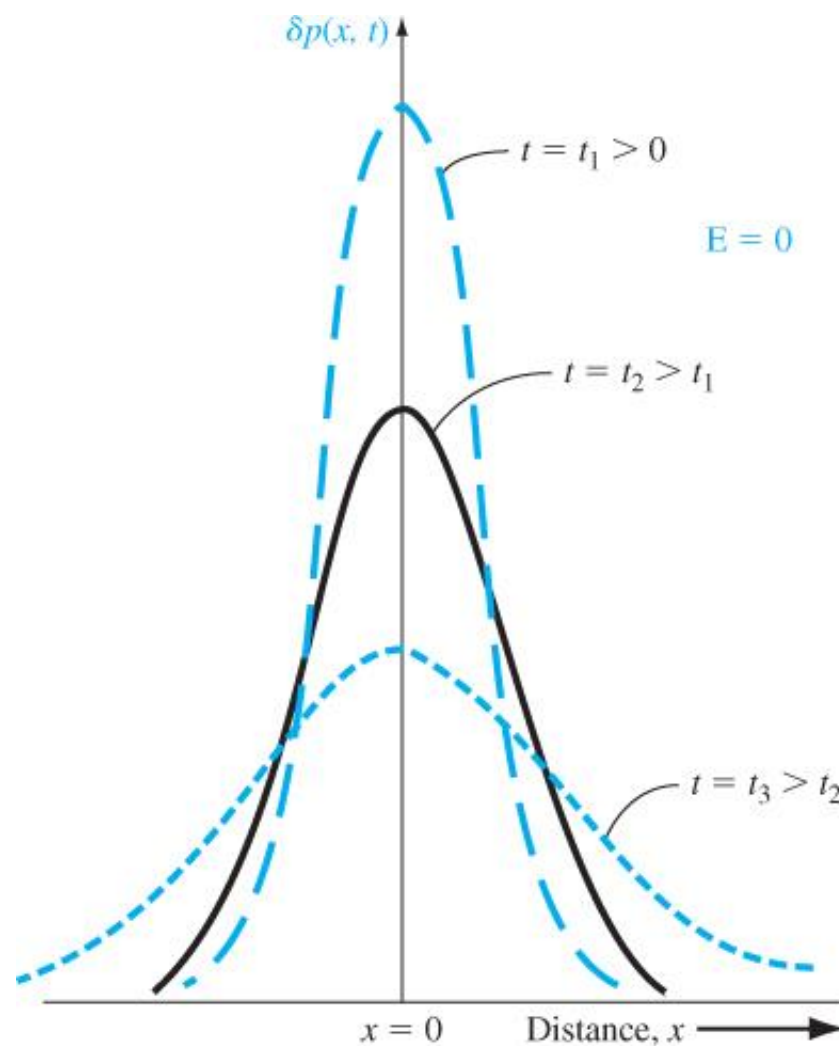


$$\frac{\partial(\delta n)}{\partial t} = D_n \frac{\partial^2(\delta n)}{\partial x^2} + \mu_n E \frac{\partial(\delta n)}{\partial x} + g' - \frac{\delta n}{\tau_{n0}}$$

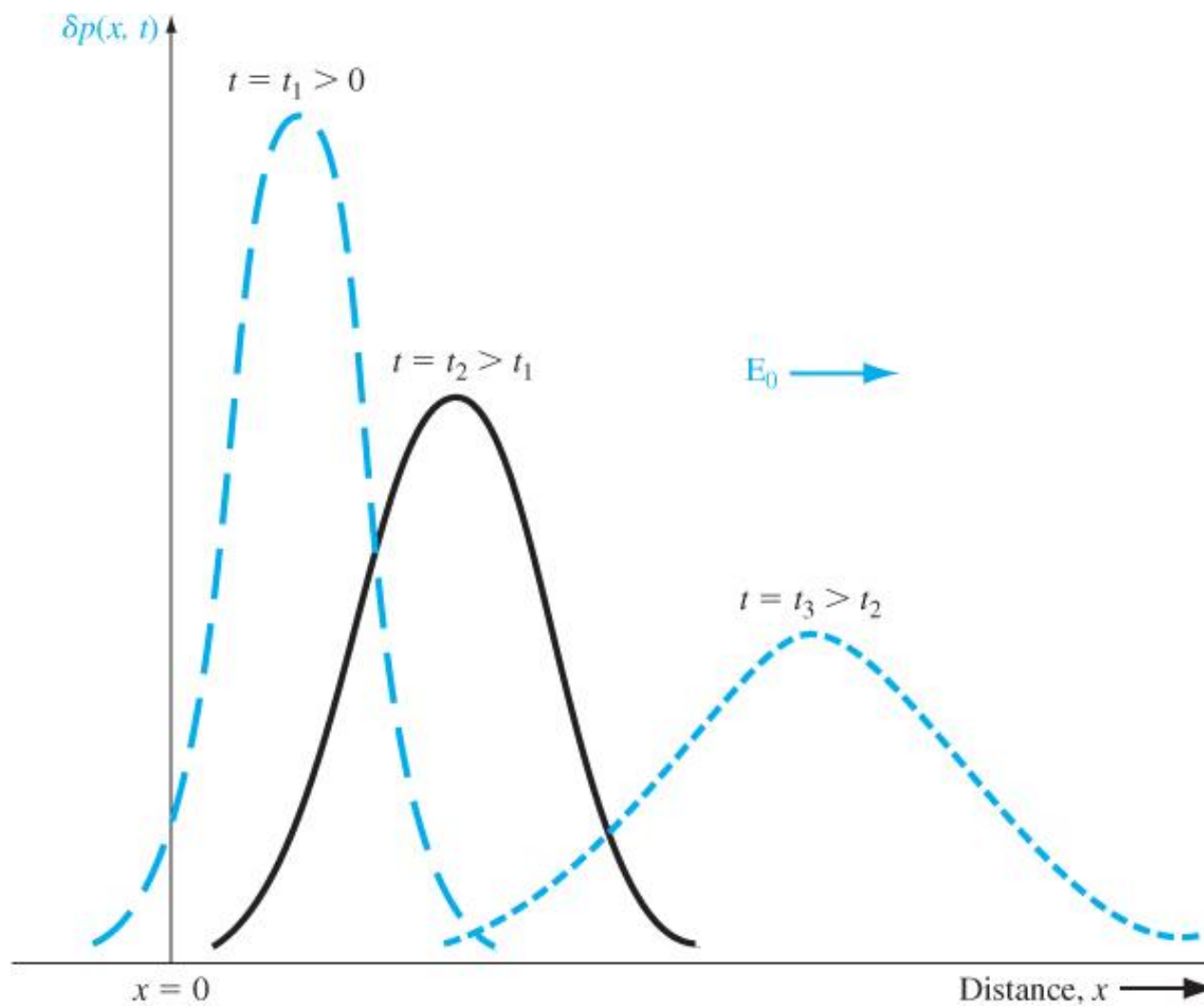
双极输运方程的应用III



双极输运方程的应用IV



双极输运方程的应用IV

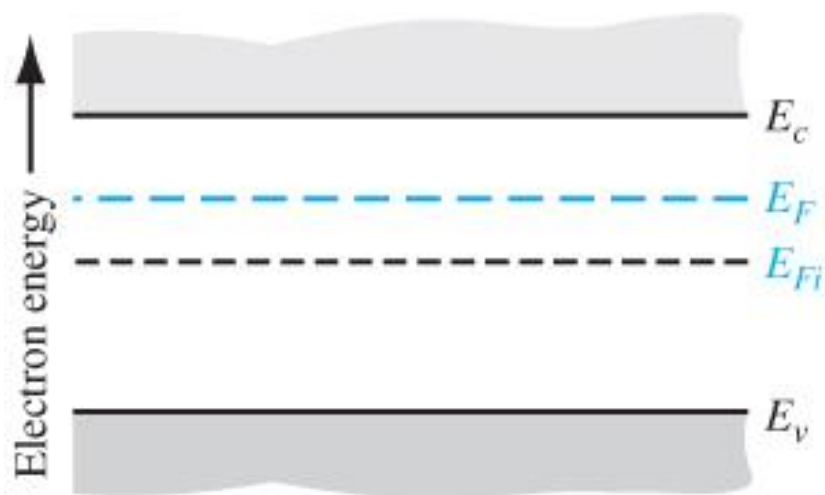


费米能级(热平衡状态)



$$n_0 = n_i \exp\left(\frac{E_F - E_{Fi}}{kT}\right)$$

$$p_0 = n_i \exp\left(\frac{E_{Fi} - E_F}{kT}\right)$$



n型

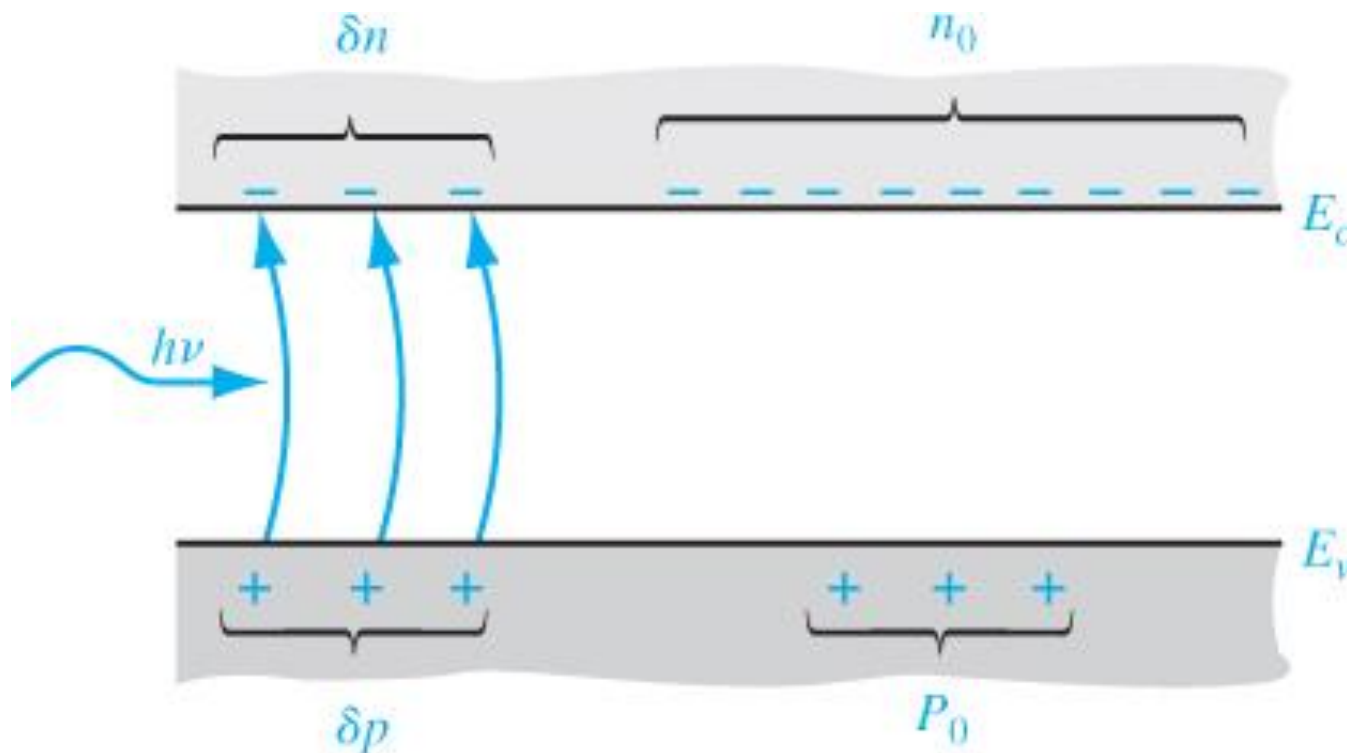


p型

非平衡过剩载流子产生



高能光子（能量大于禁带宽度）射入半导体，价带电子跃迁进入导带



$$\begin{aligned} n &= n_0 + \delta n \\ p &= p_0 + \delta p \end{aligned}$$

过剩电子、空穴

准费米能级 E_{Fn} , E_{Fp}



$$n = n_i \exp\left(\frac{E_{Fn} - E_{Fi}}{kT}\right) \quad p = n_i \exp\left(\frac{E_{Fi} - E_{Fp}}{kT}\right)$$

$$= n_i \exp\left(\frac{E_{Fn} - E_F + E_F - E_{Fi}}{kT}\right)$$

$$= n_i \exp\left(\frac{E_F - E_{Fi}}{kT}\right) \exp\left(\frac{E_{Fn} - E_F}{kT}\right)$$

$$= n_0 \exp\left(\frac{E_{Fn} - E_F}{kT}\right) \quad p = p_0 \exp\left(\frac{E_F - E_{Fp}}{kT}\right)$$

准费米能级 E_{Fn} , E_{Fp}



$$n = n_0 \exp\left(\frac{E_{Fn} - E_F}{kT}\right) \quad p = p_0 \exp\left(\frac{E_F - E_{Fp}}{kT}\right)$$

$$np = n_0 \exp\left(\frac{E_{Fn} - E_F}{kT}\right) \cdot p_0 \exp\left(\frac{E_F - E_{Fp}}{kT}\right)$$

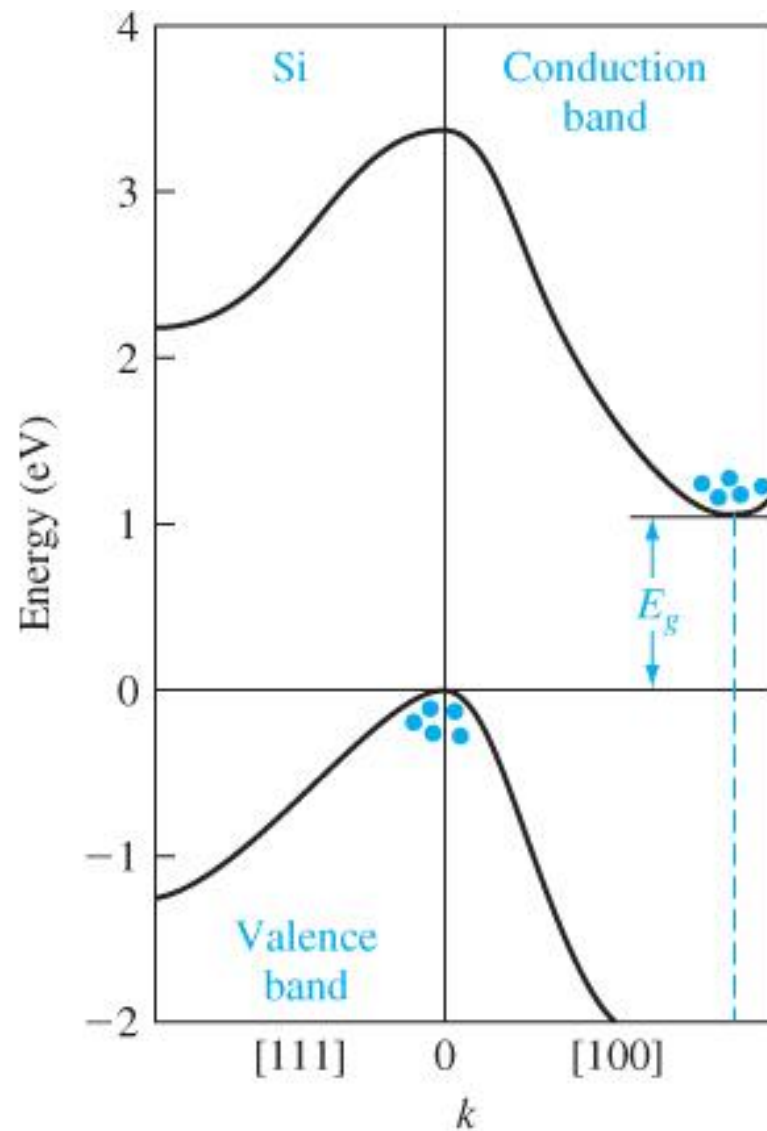
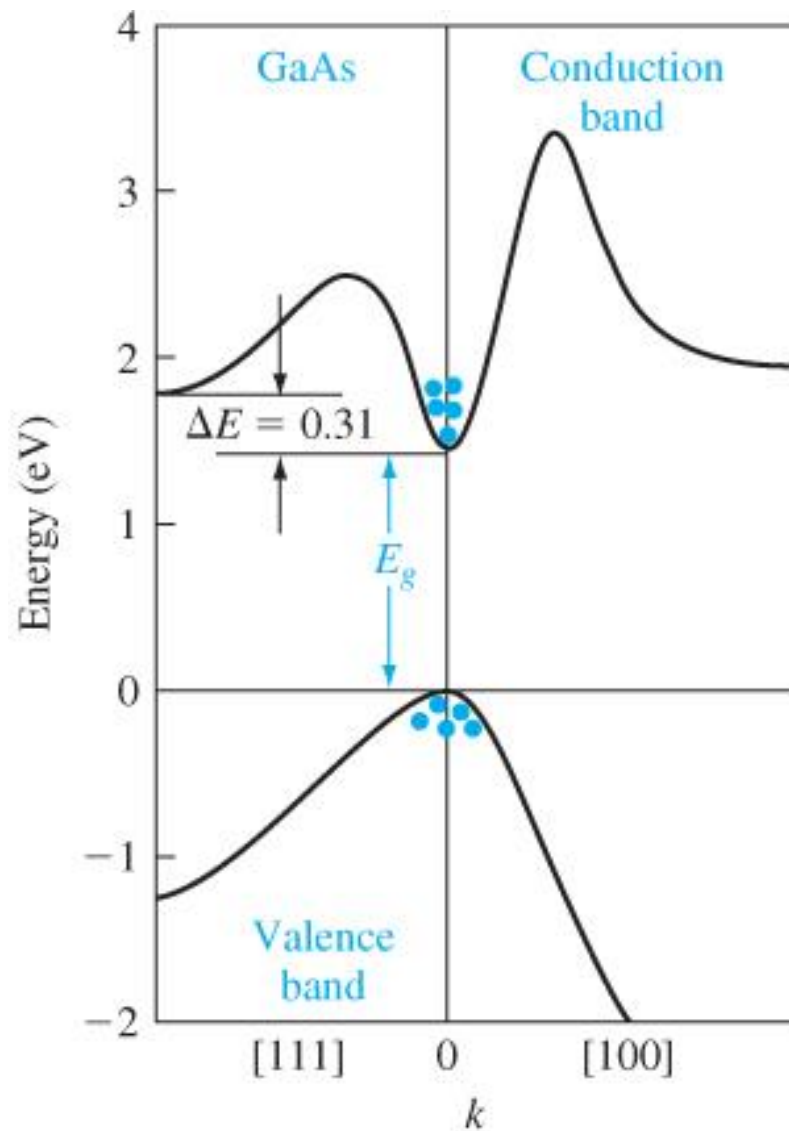
$$= n_0 p_0 \exp\left(\frac{E_{Fn} - E_{Fp}}{kT}\right)$$

$$= n_i^2 \exp\left(\frac{E_{Fn} - E_{Fp}}{kT}\right)$$

载流子复合

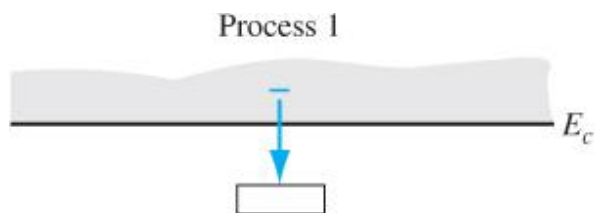


直接带隙、间接带隙半导体

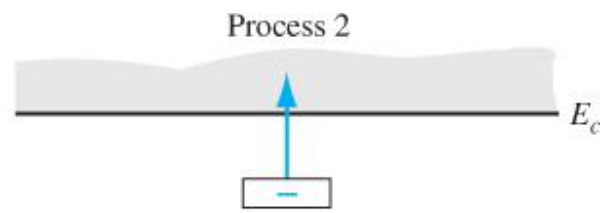


硅是间接带隙半导体，直接复合概率低，常通过复合中心间接复合。
复合中心：由于晶体中存在缺陷而在禁带中产生分立的电子能态。

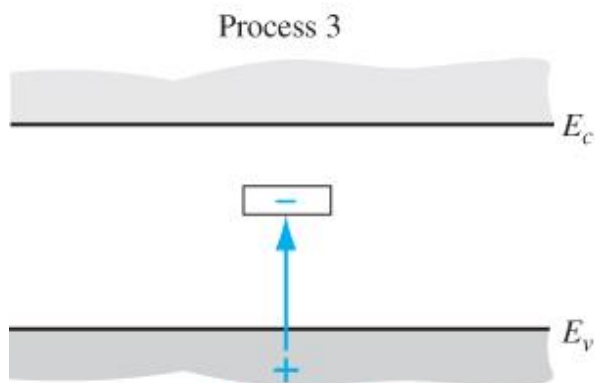
Shockley-Read-Hall (SRH) 复合理论



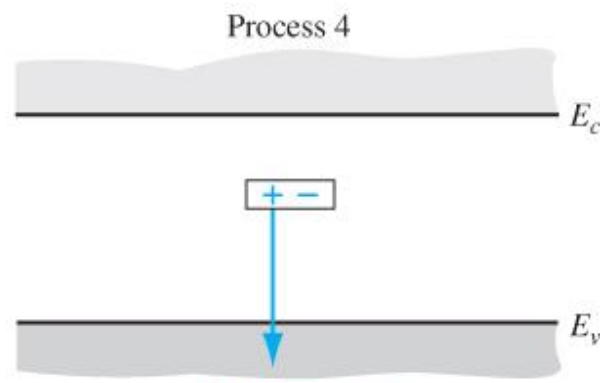
电子俘获



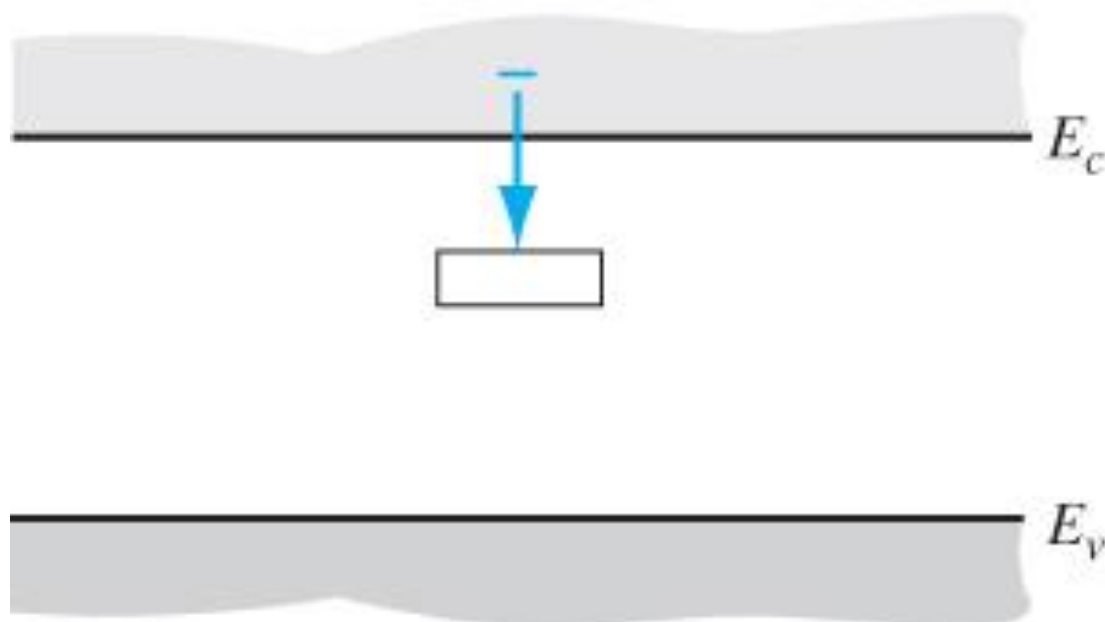
电子辐射



空穴俘获



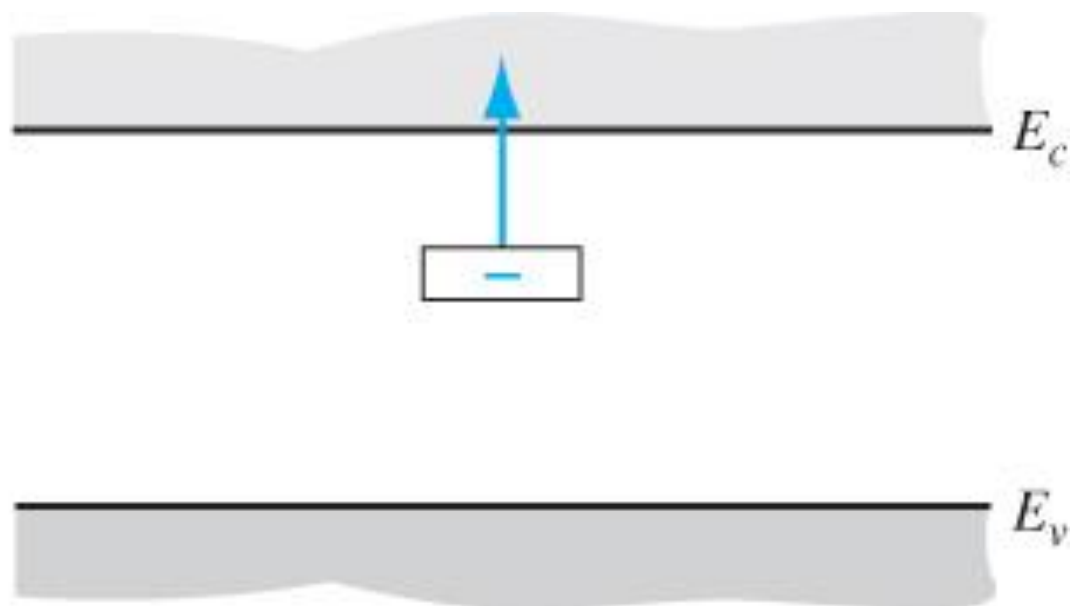
空穴辐射



电子俘获

$$R_{cn} = C_n N_t [1 - f_F(E_t)] n$$

$$f_F(E_t) = \frac{1}{1 + \exp\left(\frac{E_t - E_F}{kT}\right)}$$



电子辐射

$$R_{en} = E_n N_t f_F(E_t)$$

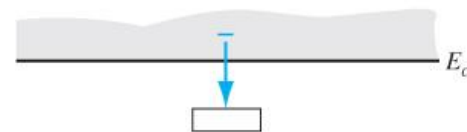
热平衡状态下:

$$R_{cn} = C_n N_t [1 - f_{F0}(E_t)] n_0$$

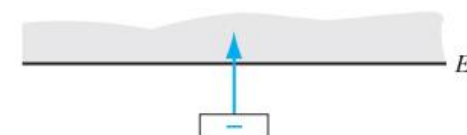
$$R_{en} = E_n N_t f_{F0}(E_t)$$

$$C_n N_t [1 - f_{F0}(E_t)] n = E_n N_t f_{F0}(E_t)$$

$$f_{F0}(E_t) = \frac{1}{1 + \exp\left(\frac{E_t - E_F}{kT}\right)} = \exp\left(-\frac{E_t - E_F}{kT}\right)$$



电子俘获



电子辐射

热平衡状态下:

$$E_n N_t f_{F0}(E_t) = C_n N_t [1 - f_{F0}(E_t)] n_0$$

$$f_{F0}(E_t) = \frac{1}{1 + \exp\left(\frac{E_t - E_F}{kT}\right)} = \exp\left(-\frac{E_t - E_F}{kT}\right)$$

$$1 - f_{F0}(E_t) = \frac{1}{1 + \exp\left(-\frac{E_t - E_F}{kT}\right)} \approx 1$$

热平衡状态下:

$$n_0 = N_C \exp\left(\frac{E_F - E_C}{kT}\right)$$

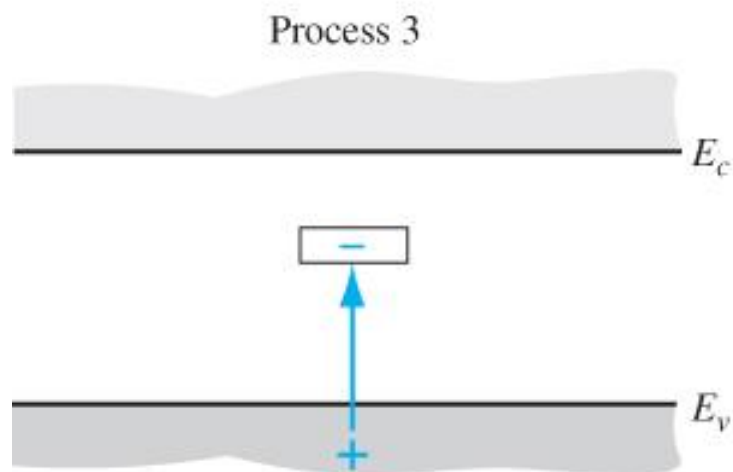
$$E_n = C_n n_0 \exp\left(\frac{E_t - E_F}{kT}\right)$$

$$= C_n N_C \exp\left(\frac{E_t - E_C}{kT}\right)$$

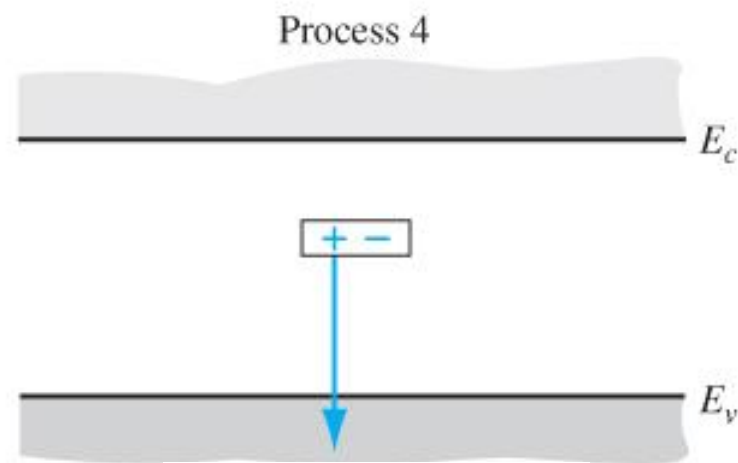
$$= C_n n' \quad n' = N_C \exp\left(\frac{E_t - E_C}{kT}\right)$$

非平衡状态下，导带电子被俘获的净概率：

$$\begin{aligned} R_n &= R_{cn} - R_{en} \\ &= C_n N_t [1 - f_F(E_t)] n - E_n N_t f_F(E_t) \\ &= C_n N_t [n(1 - f_F(E_t)) - n' f_F(E_t)] \\ n' &= N_C \exp\left(\frac{E_t - E_C}{kT}\right) \end{aligned}$$



空穴俘获



空穴辐射

非平衡状态下，价带空穴被俘获的净概率：

$$\begin{aligned}
 R_p &= R_{cp} - R_{ep} & p' &= N_v \exp\left(\frac{E_v - E_t}{kT}\right) \\
 &= C_p N_t \left[f_F(E_t) p - p' (1 - f_F(E_t)) \right]
 \end{aligned}$$

非平衡状态下，导带电子被俘获的净概率：

$$\begin{aligned} R_n &= R_{cn} - R_{en} \\ &= C_n N_t \left[n(1 - f_F(E_t)) - n' f_F(E_t) \right] \end{aligned}$$

非平衡状态下，价带空穴被俘获的净概率：

$$\begin{aligned} R_p &= R_{cp} - R_{ep} \\ &= C_p N_t \left[f_F(E_t) p - p'(1 - f_F(E_t)) \right] \end{aligned}$$

$$R_n = C_n N_t \left[n(1 - f_F(E_t)) - n' f_F(E_t) \right]$$

$$R_p = C_p N_t \left[f_F(E_t) p - p'(1 - f_F(E_t)) \right]$$

稳态情况下:

$$R_n = R_p$$

$$= \frac{C_n C_p N_t (np - n_i^2)}{C_n (n + n') + C_p (p + p')}$$

$$\begin{aligned} R_n = R_p &= \frac{C_n C_p N_t (np - n_i^2)}{C_n (n + n') + C_p (p + p')} \\ &= C_n N_t \frac{np - n_i^2}{n + n' + p + p'} \quad (C_n = C_p) \\ &= C_n N_t \frac{p - p_{n0}}{1 + \frac{(n' + p')}{n}} \quad (n \gg p) \end{aligned}$$

$$n' = N_C \exp\left(\frac{E_t - E_C}{kT}\right)$$

$$R = C_n N_t \frac{p - p_{n0}}{1 + \frac{(n' + p')}{n}}$$

$$= N_C \exp\left(\frac{E_t - E_{Fi} + E_{Fi} - E_C}{kT}\right)$$

$$= N_C \exp\left(\frac{E_{Fi} - E_C}{kT}\right) \exp\left(\frac{E_t - E_{Fi}}{kT}\right)$$

$$= n_i \exp\left(\frac{E_t - E_{Fi}}{kT}\right)$$

$$p' = N_V \exp\left(\frac{E_V - E_t}{kT}\right)$$

$$R = C_n N_t \frac{p - p_{n0}}{1 + \frac{(n' + p')}{n}}$$

$$= N_V \exp\left(\frac{E_V - E_{Fi} + E_{Fi} - E_t}{kT}\right)$$

$$= N_V \exp\left(\frac{E_V - E_{Fi}}{kT}\right) \exp\left(\frac{E_{Fi} - E_t}{kT}\right)$$

$$= n_i \exp\left(\frac{E_{Fi} - E_t}{kT}\right)$$

$$R = C_n N_t \frac{p - p_{n0}}{1 + \frac{(n' + p')}{n}}$$

$$p' = n_i \exp\left(\frac{E_{Fi} - E_t}{kT}\right)$$

$$n' = n_i \exp\left(\frac{E_t - E_{Fi}}{kT}\right)$$

$$= C_n N_t \frac{p - p_{n0}}{1 + \frac{n_i}{n} \left(\exp\left(\frac{E_{Fi} - E_t}{kT}\right) + \exp\left(\frac{E_t - E_{Fi}}{kT}\right) \right)}$$

$$= C_n N_t \frac{p - p_{n0}}{1 + 2 \left(\frac{n_i}{n} \right) \cosh\left(\frac{E_{Fi} - E_t}{kT}\right)}$$

$$R = C_n N_t \frac{p - p_{n0}}{1 + 2 \left(\frac{n_i}{n} \right) \cosh \left(\frac{E_{Fi} - E_t}{kT} \right)}$$

小注入下n型半导体:

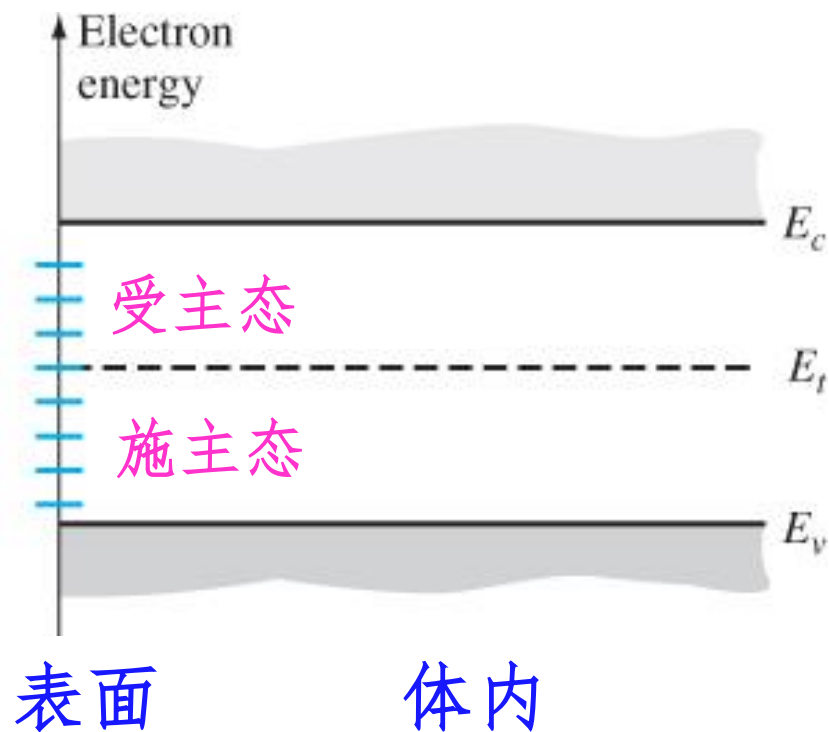
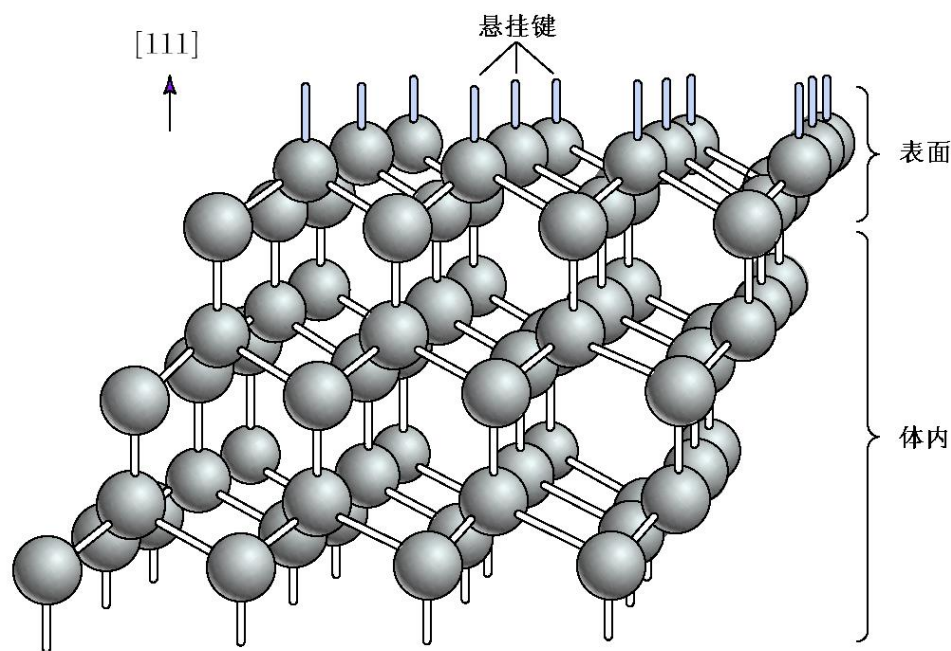
$$\begin{aligned} R &= C_p N_t \delta p \\ &= \frac{\delta p}{1 / C_p N_t} = \frac{\delta p}{\tau_{p0}} \end{aligned}$$

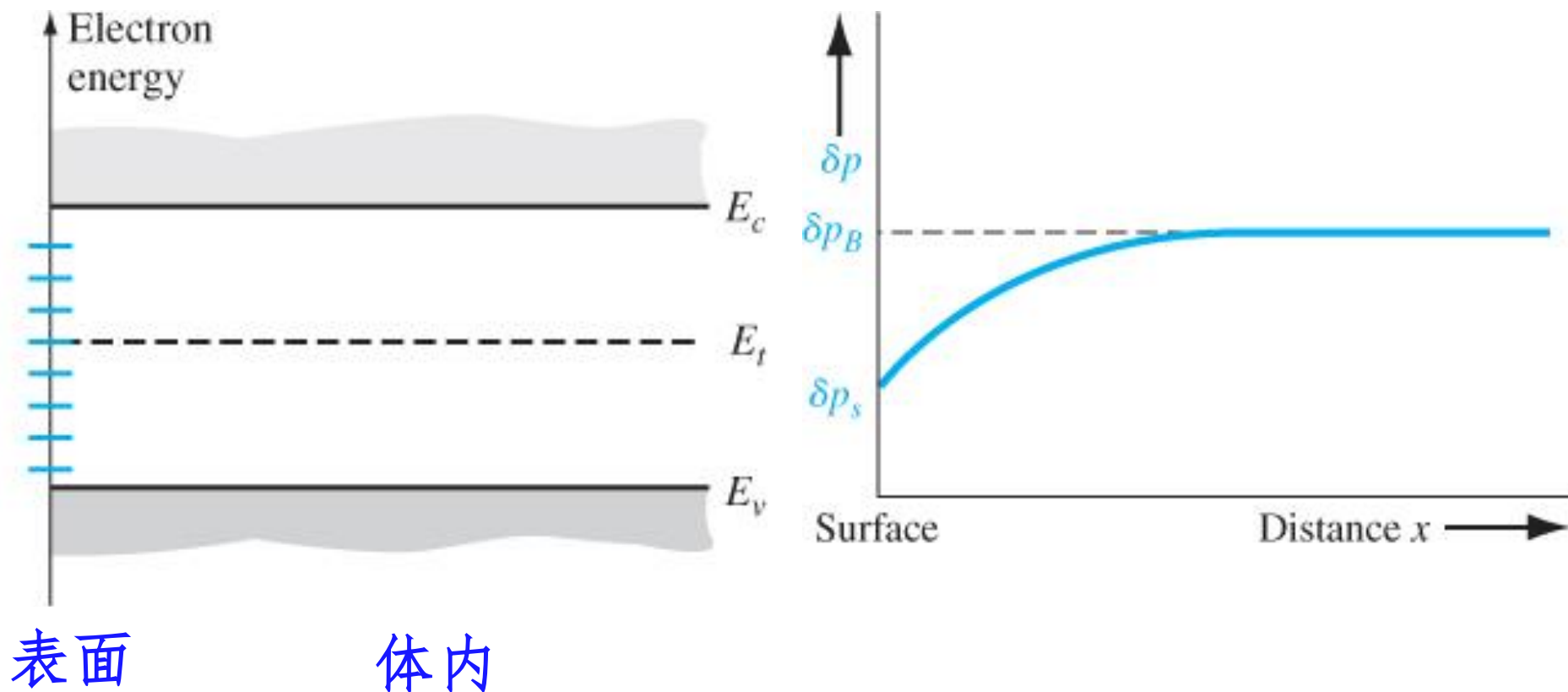
小注入下p型半导体:

$$\begin{aligned} R &= C_n N_t \delta n \\ &= \frac{\delta n}{1 / C_n N_t} = \frac{\delta n}{\tau_{n0}} \end{aligned}$$

表面态:

由于在晶体结构在表面中断,产生局部的能态(产生-复合中心).





- 1) 产生 (Generation)、复合 (Recombination), 直接、间接
- 2) 产生率、复合率
- 3) 非平衡态 (光照、辐射、施加电压等)
- 4) 过剩载流子的产生与复合
 - 过剩载流子 ($\delta n, \delta p$)
 - 载流子的总浓度 ($n = n_0 + \delta n, p = p_0 + \delta p$)
 - 小注入 (过剩载流子浓度远小于热平衡多子浓度)
- 5) 连续性方程
- 6) 双极输运方程
- 7) 准费米能级 (E_{Fn}, E_{Fp})
- 8) Shockley-Read-Hall (SRH) 复合理论
- 9) 表面复合